METHOD OF OPTIMIZING FOCUS OF OPTICAL INSPECTION APPARATUS AND METHOD AND APPARATUS OF DETECTING DEFECTS USING THE SAME

ABSTRACT OF THE DISCLOSURE

According to a method of optimizing a focus of an optical inspection apparatus, a first light is irradiated onto a substrate. Then, the first light is reflected on the substrate to form a second light. The second light is sensed with various foci to form image information corresponding to each of the foci. Then, a relation between foci of the optical inspection apparatus and gain value corresponding to the image information is obtained. Then, the focus corresponding to a minimum gain value is set up as an optimized focus. Thus, a focus of an optical inspection apparatus is accurately adjusted to enhance efficiency of defecting defects, so that defects of semiconductor apparatus are more accurately detected.